

Form PTO 1449 U.S. Department of Commerce
 Rev. 7-80 Patent and Trademark Office
LIST OF PRIOR ART CITED BY APPLICANT
 (Use Several Sheets If Necessary)

Atty. Docket No. CH9498US Serial No.
 Applicant Jagdish Narayan et al To Be Assigned
 Filing Date Herewith Group No.

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
AA	3,808,109	04/30/74	Schauer	204	38 A	
AB	3,878,079	04/15/75	Schauer	204	192	
AC	4,036,708	07/19/77	Feit et al	204	38	
AD	5,281,485	01/25/94	Colgan et al	428	457	
AE	5,406,123	04/11/95	Narayan	257	767	
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AH	6,291,885 B1	09/18/01	Cabral, Jr. et al	257	751	
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		"Epitaxial growth of TiN films on (100) silicon substrates by laser physical vapor deposition"
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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /JL/

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